

Silyloxyamines as Sources of Silyl Radicals: ESR Spin Trapping, Laser Flash Photolysis Investigation and Photopolymerization Ability

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David-Louis Versace, Mohamad Ali Tehfe, Jacques Lalevée, Virginie Casarotto, Nicolas Blanchard, et al.. Silyloxyamines as Sources of Silyl Radicals: ESR Spin Trapping, Laser Flash Photolysis Investigation and Photopolymerization Ability. Journal of Physical Organic Chemistry, 2010, 24 (4), pp.342. 10.1002/poc.1762 hal-00599801

HAL Id: hal-00599801 https://hal.science/hal-00599801

Submitted on 11 Jun 2011

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Journal of Physical Organic Chemistry

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Journal:	Journal of Physical Organic Chemistry
Manuscript ID:	POC-10-0040.R3
Wiley - Manuscript type:	Research Article
Date Submitted by the Author:	27-May-2010
Complete List of Authors:	Lalevee, Jacques; Ecole Nationale Superieure de Chimie de Mulhouse, Department of Photochemistry
Keywords:	Silyl Radicals, Photoinitiators, ESR spin-trapping, Photopolymerization, Laser Flash Photolysis



Supporting Information for:

Silyloxyamines as Sources of Silyl Radicals: ESR Spin Trapping, Laser Flash Photolysis Investigation and Photopolymerization Ability.

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For purification, the chromatographic technique described by Still (J. Org. Chem. 1978, 43, 2923-2925) was selected.

Figures 1-3. ¹H (400M Hz), ¹³C (100M Hz) and DEPT NMR spectra for SiN1.

Figures 2-5. ¹H (400M Hz), ¹³C (100M Hz) NMR spectra for **SiN2**.

Z-Matrix for SiN1 and SiN2.

Figure 1.

Chemical Formula: C₁₇H₂₉NOSi₂ Molecular Weight: 319,59 (CDCI₃; 400 MHz) ⊐- 7.77]- 5.66 ч ц L L ${\bf l}_{\rm max}$ - 4.16 - 1.00 - 0.98 - 4.00 - 4.01 Т 3.0 Т Τ Τ Т Т т т Т 8.0 ppm (f1) 7.0 6.0 5.0 4.0 2.0 1.0 0.0











4 5 Z-Matrix for SiN1 and SiN2:

6					
7					
8	С				
9	C	1	B1		
10	С	1	B2 2	A1	D 4
10	H	1	B3 Z	AZ 3	DI
11	C	2	B4 1	A3 3	D2
12	L L	3	B5 1 B6 1	A4 Z	D3
13	п	2	BO 1 B7 1	A5 3	
14	п С	5	B/ 1 D0 2	A0 2	
15	N	5		A7 1 A9 1	
16	0	5	B10 3	A0 1	20
10	C	10	B10 5 B11 5	Δ10 2	00
17	C C	10	B12 5	Δ11 2	D10
18	Si	11	B13 6	A12 3	D10
19	H	9	B14 6	A13 3	D12
20	C	12	B15 10	A14 5	D13
21	C	13	B16 10	A15 5	D14
22	C	14	B17 11	A16 6	D15
22	С	14	B18 11	A17 6	D16
23	Si	14	B19 11	A18 6	D17
24	н	12	B20 10	A19 5	D18
25	н	12	B21 10	A20 5	D19
26	Н	13	B22 10	A21 5	D20
27	Н	13	B23 10	A22 5	D21
28	С	20	B24 14	A23 11	D22
20	С	20	B25 14	A24 11	D23
20	С	20	B26 14	A25 11	D24
30	Н	16	B27 12	A26 10	D25
31	н	16	B28 12	A27 10	D26
32	н	16	B29 12	A28 10	D27
33	н	17	B30 13	A29 10	D28
34	н	17	B31 13	A30 10	D29
35	н	1/	B32 13	A31 10	D30
36	н	18	B33 14	A32 11	D31
27	п	10	D34 14 D25 14	A33 11	220
37	н	10	B36 14	A34 11 A35 11	D37
38	н	19	B37 14	A35 11 A36 11	D34
39	н	19	B38 14	A37 11	D36
40	Н	25	B39 20	A38 14	D37
41	н	25	B40 20	A39 14	D38
42	н	25	B41 20	A40 14	D39
43	н	26	B42 20	A41 14	D40
40	н	26	B43 20	A42 14	D41
44	н	26	B44 20	A43 14	D42
45	Н	27	B45 20	A44 14	D43
46	н	27	B46 20	A45 14	D44
47	н	27	B47 20	A46 14	D45
48					
49	B1	1.392	01640		
50	B2	1.393	78782		
51 51	B3	1.090	78921		
51	B4	1.414	16569		
52	B5	1.397	99046		
53	BO	1.087	4/125		
54	B7	1.08/	74922		
55	BO	1.394	2002		
56	65 R10	1 201	121659		
57	R11	1 450	581053		
59	R12	1 456	592757		
50	B13	1.69	558897		
59	B14	1.08	578969		
60	B15	1.53	309618		
	B16	1.53	328407		
	B17	1.89	522017		

1		
2		
3	B18	1.89684001
5	B19 B20	1.09217964
6	B21	1.10110337
7	B22	1.09237008
8	В23 В24	1.10102472
9	B25	1.90222071
10	B26	1.90071664
11	B27	1.09688129
12	B28 B29	1.09621648
13	B30	1.09693896
14	B31	1.09612521
15	В32 В33	1.09840409
17	B34	1.09671481
18	B35	1.09721149
19	B36	1.09836505
20	B38	1.09713382
21	B39	1.09832852
22	B40	1.09731825
23	B41	1.09715526
24	B42	1.09705351
25	B44	1.09676968
26	B45	1.09804137
27	B46	1.09647633
28	A1	121.72864056
29	A2	118.96964042
30	A3	120.49782825
31	A4 A5	118.12096436
32	A6	121.95878758
33	A7	121.09450848
34 25	A8	121.29457917
30	A9 A10	121,56022237
37	A11	121.70196996
38	A12	126.31119745
39	A13	117.78784528
40	A14 A15	115.07164457
41	A16	109.90152077
42	A17	109.83991705
43	A18	103.50037223
44	A19 A20	108.88821873
45	A21	108.01705494
46	A22	108.81604921
47	A23 A24	109.17791337
48	A25	110.17567822
49	A26	110.18579519
50	A27	111.99084817
51	A28 A29	110.20668223
52 52	A30	111.97766105
55	A31	111.26876274
55	A32	110.63530545
56	A33 A34	111.80021088
57	A35	110.44165343
58	A36	111.66252310
59	A37	112.13783144
60	A30	111.94515183
	A40	111.99063234
	A41	111.11711069

$ \begin{array}{c} 1 \\ 2 \\ 3 \\ 4 \\ 5 \\ 6 \\ 7 \\ 8 \\ 9 \\ 10 \\ 11 \\ 12 \\ 13 \\ 14 \\ 15 \\ 16 \\ 17 \\ 18 \\ 19 \\ 20 \\ 21 \\ 22 \\ 23 \\ 24 \\ 25 \\ 26 \\ \end{array} $	A42 A43 A44 A45 A46 D1 D2 D3 D4 D5 D6 D7 D8 D9 D10 D11 D12 D13 D14 D15 D16 D17 D18 D14 D15 D16 D17 D18 D19 D20 D21 D22 D23	111.894 111.275 111.247 111.119 111.842 -179.161 -0.9854 0.32709 177.2513 179.175 0.73833 -178.799 176.272 21.1133 -159.576 89.5673 175.070 -103.738 -102.669 -65.146 53.6766 174.480 19.1844 133.230 20.286 134.300 174.679 -65.683	93490 80285 (69763 51271 75563 39097 6026 9334 82173 64963 83927 60837 70505 4167 527998 85854 959065 837100 940907 53065 53065 53065 53065 106799 1060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060511 060515 05755 05755 057555 0575555555555555			
27 28	D24 D25	-179.847	789861			
29	D26 D27	-60.446 59.991	31633 56046			
30	D28	-179.711	18324			
31	D29 D30	-60.319 60.114	95332 71745			
32	D31	-177.560	05565			
30 34	D32	-57.942	91120			
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36	D35	-62.262	46844			
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40	D40 D41	178.877	'86606 71887			
41	D41 D42	59.068	11365			
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44	D44	-59.387	/684/			
45						
46	c	1	D1			
47	c	1	B1 B2 2	A1		
48	н	1	B3 2	A2 3	D1	
49 50	C C	2	B4 1	A3 3	D2	
51	0	3	B5 1 B6 1	A4 2 A5 2	D3 D4	
52	н	2	B7 1	A6 3	D5	
53	C C	6	B8 3	A7 1	D6 D7	
54	c	5	B10 2	A9 1	D8	
55	Si	7	B11 3	A10 1	D9	
56 57	C N	10 0	B12 6	A11 3	D10 D11	
ວ/ 58	C	11	B14 5	A13 2	D12	
59	С	12	B15 7	A14 3	D13	
60	C Si	12 12	B16 7 B17 7	A15 3	D14	
00	H	10	B17 / B18 6	A10 3 A17 3	D16	
	н	10	B19 6	A18 3	D17	

A19 2

A20 2

A21 6

A22 6

A23 7

A24 7

A25 7

A26 6

A27 6

A28 5

A29 5

A30 7

A31 7

A32 7

A33 7

A34 7

A35 7

A36 9

A37 9

A38 9

A39 9

A40 12

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D45

2				
3	н	11	B20	5
4	Н	11	B21	5
5	С	14	B22	9
6	C	14	B23	9
7	C	18 18	B24 B25	12
8	c	18	B26	12
9	н	13	B27	10
10	н	13	B28	10
11	Н	15	B29	11
12	н	15	B30	11
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14	н	16	B33	12
15	н	17	B34	12
16	н	17	B35	12
17	Н	17	B36	12
18	H	23	B37	14
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20	н	24	B40	14
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22	Н	25	B42	18
23	Н	25	B43	18
24	н ц	26	B44	18
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26	н	27	B47	18
20 27	н	27	B48	18
28	н	27	B49	18
29	D1	1 20170	70	
30	B1 B2	1.391/60)70)34	
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33	B5	1.403076	527	
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35	B7	1.088515	030 040	
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38	B11	1.69948	748	
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41 42	B16	1.89430	631	
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40 17	B22	1.45605	668	
47 48	B23	1.45664	359	
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49 50	B25	1.90182	536	
50	B20 B27	1.90084	205 101	
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52	B29	1.09620	306	
55	B30	1.09697	843	
55	B31	1.09790	916	
55	B32	1.09610	162	
57	633 R34	1.09596	590	
57	B35	1.09725	939	
50	B36	1.09672	263	
29	B37	1.09634	466	
Ud	B38	1.10671	572	
	B39	1.10692	012	
	в40	1.09656	23/	

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20	A12	119.97368454
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37	A32	112.36362490
38	A33	111.88027965
39	A34 Δ35	110.79275956
40	A36	107.69173214
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54 55	D5	-179.92231746
56	D6 D7	0.46143949
57	D8	-178.16670260
58	D9	55.42182531
59	D10	164.56350594
60	D12	-1/8.84303413
	D13	-70.70576050
	D14	49.11862850

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D20	-18.33010178	
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DZZ	1/5.41/48526	
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D24	55.60356526	
D25	-/5.2/6/0514	
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D28	/2.39/44299	
D29	-169.114/6386	
D30	-50.00843616	
D31	/1.42082545	
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D33	-177.78504214	
D34	-58.31962928	
D35	168.37553697	
D36	-74.57727096	
D37	77.10040458	
D38	-166.00991355	
D39	-179.84327306	
D40	-60.21486370	
D41	60.44062153	
D42	179.08691466	
D43	-61.08262253	
D44	59.24049388	
D45	-177.92233658	
D46	-57.85513639	

Silyloxyamines as Sources of Silyl Radicals: ESR Spin Trapping, Laser Flash Photolysis Investigation and Photopolymerization Ability.

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Abstract:

Two silyloxyamines derived from 8-(pentamethyldisilyloxy)-julolidine and diethyl 3-(pentamethyldisilyloxy)-aniline are proposed as new sources of silyl radicals. The decomposition mechanism, excited state processes and the radical generation are explored by steady state photolysis, laser flash photolysis, ESR and MO calculations. The Si-Si bond cleavage is clearly demonstrated. The formation of a radical cation on the amine moiety is also observed. Moreover, these compounds work as efficient Type I and Type II photoinitiators of free radical photopolymerization.

Keywords: Silyl Radicals, Laser Flash Photolysis, ESR spin-trapping, Photopolymerization, Photoinitiators.

Introduction:

The development of silyl functionalized compounds and silyl radical sources is now the subject of many efforts in organic chemistry.^[1-2] In particular, the bulky tris(trimethylsilyl)silyl group has been found to promote [2+2] cyclizations^[2b] and Mukaiyama aldol reactions.^[2c] In addition, the silyloxy compounds derived from tris(trimethylsilyl)silane ("super silyl ethers") can be used as interesting UV-labile silyl protecting groups of alcohols ^[1-2] (Scheme 1 where R stands for a large diversity of substituents). This photocleavage provides an alternative approach to the classical thermal deprotection.³ However, little is known on the photochemical mechanisms associated with such a reaction; this process can involve photogeneration of silyl radicals.



The silyl radical chemistry which is now the subject of numerous studies ^[4-12] appears highly worthwhile for the development of new mono- and bi-component sources of silyl radicals R₃Si[•] usable as photoinitiators (PI) for free radical photopolymerization (FRP): indeed, silyl radicals are highly valuable to overcome the oxygen inhibition usually observed in FRP.^[7-12] In this area, the production of R₃Si[•] was first achieved through the photodegradation of polysilane polymers that occurs *via* a Si-Si bond cleavage ^[4-6] or the use of photosensitizer/silane couples. New compounds based on Si-Si, C-Si or S-Si single bond cleavage and leading to R₃Si[•] have been also recently proposed.^[7-12] On this occasion, their ability as Type I photoinitiating systems to initiate both FRP and free radical promoted cationic polymerization (FRPCP) was underlined.

The design and the development of new PIs from silyl containing compounds exhibiting novel properties remain of great interest. The aim of the present paper is to introduce new sources of silyl radicals based on the design of silyloxyamines having easy and convenient synthetic procedures. The new proposed structures could be useful for FRP. The limited access and stability of phenoxy tris(trimethylsilyl)silanes led us to investigate alternative compounds such as new silyloxyamines derived from pentamethyldisilane.^[3] Two starting structures (8-hydroxyjulolidine and 3-diethylaminophenol) have been selected for the synthesis of the corresponding silyloxyamines (Scheme 2): silyloxyjulolidine (**SiN1**), silyloxyaniline (**SiN2**). In contrast with other silyl sources previously developed and built on a carbonyl chromophore, these molecules are expected to possess a charge transfer transition

 (the donor being the amine and the acceptor the silyl ether group) allowing a tunable red-shift of the absorption through a relatively easy introduction of various amine skeletons. This could help in the design of efficient longer wavelength absorbing PIs for less toxic irradiation lamps.^[11-12]

Through laser flash photolysis (LFP), Electron Spin Resonance Spin-Trapping (ESR-ST) and quantum mechanical calculations, we will evaluate the silyl radical formation upon UV irradiation, investigate the photopolymerization ability of these silyloxyamines by Real-Time FTIR and propose a mechanism for the initiation step of the acrylate photopolymerization.



Experimental part and computational procedure:

1/ Samples:

8-hydroxyjulolidine and 3-diethylaminophenol were purchased from Aldrich and used with the best purity available. Chloropentamethyldisilane was purchased from Aldrich and used as received. Benzophenone (BP) was used as reference type II photoinitiator (Aldrich). Ethyldimethylaminobenzoate (EDB-Esacure from Lamberti) and Tris(trimethylsilyI)silane (TTMSS - Aldrich) were chosen as reference co-initiators.

2/ Synthesis procedures for SiN1 and SIN2:

Synthesis of SiN1:

To a solution of 8-hydroxyjulolidine (0.1 g, 0.53 mmol) in CH_2Cl_2 (0.5 mL) were added DMAP (10 mol%, 6.5 mg), *i*-PrNEt₂ (0.18 mL, 1.06 mmol) and chloropentamethyldisilane (0.16 mL, 0.84 mmol). After 48 h, a conversion of 70% was reached as indicated by TLC analysis (cyclohexane/ethyl acetate = 85:15). The reaction mixture was concentrated under vacuum and the residual oil was adsorbed on silica gel using CH_2Cl_2 . The dried solid was then loaded on silica gel and eluted with cyclohexane/ethyl acetate = 100:3 following the

rapid chromatographic technique (see supporting information). The desired product eluted first (clearly different from 8-hydroxyjulolidine by silica coated thin layer chromatography analysis) and was obtained as colorless oil (0.10 g, 59%). A copy of the ¹H and ¹³C NMR Spectra is provided as supplementary material. The estimated purity is > 95%. From the UV spectra and taking into account that the visible absorption of the starting compound (8-hydroxyjulolidine) completely disappears; the presence of this starting compound in the final purified product is < 0.5%.

¹H NMR (CDCl₃, 400 MHz, 298 K) δ 6.64 (d, J = 7.9 Hz, 1H); 6.07 (d, J = 7.9 Hz, 1H); 3.08 (p, J = 5.5 Hz, 4H), 2.71 (t, J = 6.5 Hz, 2H); 2.63 (t, J = 6.5 Hz, 2H); 1.99-1.92 (4H); 0.36 (s, 6H); 0.10 (s, 9H). ¹³C NMR (100 MHz, CDCl₃, 298 K) δ 152.2; 146.1; 126.2; 114.7; 112.5; 106.6; 50.2; 49.8; 27.2; 22.4; 21.94; 21.86; 2.08; -2.2.

Synthesis of SiN2:

To a solution of 3-diethylaminophenol (0.15 g, 0.9 mmol) in CH₂Cl₂ (1 mL) were added DMAP (10 mol%), *i*-PrNEt₂ (0.32 mL, 1.8 mmol) and chloropentamethyldisilane (0.2 mL, 1 mmol). Monitoring the progress of the reaction by silica gel thin layer chromatography was difficult as SiN2 is prone to desilylation on prolonged contact with SiO₂. Therefore, after 12h the reaction mixture was concentrated under vacuum and the residual oil was adsorbed on neutral alumina using CH₂Cl₂. The dried solid was then loaded on a small pad of silica gel and eluted quickly with cyclohexane/ethyl acetate = 100:5. The desired product eluted first (clearly different from 3-diethylaminophenol by alumina coated thin layer chromatography analysis) and was obtained as colorless oil (0.21 g, 79%). A copy of the ¹H and ¹³C NMR Spectra is provided as supplementary material. The estimated purity is > 95%. From the UV spectra and taking into account that the visible absorption of the starting compound (3-diethylaminophenol) completely disappears; the presence of this starting compound in the final purified product is < 0.5%.

¹H NMR (CDCl₃, 300 MHz, 298 K) δ 7.03 (t, J = 8.1 Hz, 1H); 6.30 (d, J = 7.2 Hz, 1H); 6.17-6.12 (2H); 3.31 (q, J = 6.9 Hz, 4H); 1.15 (t, J = 6.9 Hz, 6H); 0.37 (s, 6H), 0.08 (s, 9H). ¹³C NMR (75 MHz, CDCl₃, 298 K) δ 157.2; 149.2; 129.6; 107.0; 105.4; 103.7; 44.3; 12.6; 0.2; -2.2.

3/ Polymerization experiments:

For the film photopolymerization (20 μ m thick film), a given silyloxyamine photoinitiator (3% w/w; weight concentration with respect to the monomer) was dissolved in the polymerizable triacrylate monomer (trimethylolpropane triacrylate TMPTA from Cytec). The laminated or oxygenated films deposited on a BaF₂ chip were irradiated with the

polychromatic light of a Xe lamp (filtered at $\lambda > 390$ nm; light intensity = 60 mW/cm² in the 390 < λ < 800 nm range) or a polychromatic light of a Xe-Hg lamp (L8252, Hamamasu; 150 W; light intensity = 44 mW/cm² in the 300-400 nm range). The polymerization kinetics of TMPTA were examined by measuring the consumption of monomer in photoinitiated experiments. The polymerization efficiencies of the photoinitiating systems were studied by measuring the percent conversion of TMPTA as a function of time. The evolution of the monomer double bond absorption at about 1630 cm⁻¹ was continuously followed by Real-Time FTIR spectroscopy (Nexus 870, Nicolet) as described in [9-13 and references therein].

4/ Silyloxyamines absorption spectra:

The UV-Visible absorption spectra (200-600 nm) in acetonitrile were performed in a Beckman DU-640 Spectrophotometer. Solutions were filled into a 1-cm UV path cell.

5/ Laser Flash Photolysis:

The nanosecond transient absorption setup working at 355 nm is based on a nanosecond Nd:YAG laser (Powerlite 9010, Continuum) operating at 10 Hz with an energy decreased down to about 10 mJ/ pulse at 266 nm. The analyzing system (LP900, Edinburgh Instruments) used a 450-W pulsed xenon arc lamp, a Czerny-Turner monochromator, a fast photomultiplier and a transient digitizer (TDS 340, Tektronix). The beam irradiated a 1-cm cell containing the PI. Measurements were done at room temperature. Before each measurement, solutions were degassed by argon bubbling.^[8]

6/ ESR Spin-Trapping:

Electron Spin Resonance (ESR)-Spin Trapping experiments were carried out using a X-Band spectrometer (MS 200 Magnettech). The radicals generated under light irradiation (Xe-Hg lamp –Hamamatsu L8252, 150 W; λ >310 nm) were trapped by phenyl-N-tbutylnitrone (PBN, Assay ~98%, Aldrich). This technique is useful for the identification of the radical center.^[14a-b,d] The ESR spectra simulations were carried out with the PEST WINSIM program.^[14c]

7/ Cyclic Voltammetry:

The redox potentials were measured in acetonitrile by cyclic voltammetry with tetrabutyl ammonium hexafluorophosphate (0.1 M) as a supporting electrolyte. The working electrode was a platinum disc and the reference one, a saturated calomel electrode (SCE). Ferrocene was used as a standard reference ($E_{ox} = + 0.44V/SCE$). The free-energy changes (ΔG_{Et}) for

the electron transfer from the free radical to the triplet energy acceptor can be calculated from the classical Rehm-Weller equation^[15] (Eq. 1) where E_{ox} is the oxidation potential of the donor, E_{red} the reduction potential of the acceptor, E_T the triplet state energy, C a coulombic term for the initially formed ion pair (C is neglected here as usually done in polar solvents).

$$\Delta G_{Et} = E_{Ox} - E_{\text{Re}d} - E_T + C$$
 Eq. 1

8/ Computational procedure:

All the calculations were performed using the hybrid functional B3LYP from the Gaussian 03 suite of program.^[16] The different structures were fully optimized in the Density Functional Theory framework. The Bond Dissociation Energies (BDE) and the triplet state energy (E_T) were calculated at the UB3LYP/6-31G* level. The electronic absorption spectra for the radical cations were calculated with the time-dependent density functional theory at UB3LYP/6-311G** level on the relaxed geometries.

Results and discussion:

1/ Absorption properties and molecular orbitals involved:

The UV absorption properties of **SiN1** and **SiN2** as well as 8-hydroxyjulolidine and 3diethylaminophenol in acetonitrile are displayed in Figure 1. The maximum absorption wavelengths are summarized in Table 1. The starting amino alcohols show a broad band between 350 and 600 nm which disappears in silyloxyamines (Figure 1).

Figure 2 describes the HOMOs and LUMOs orbitals of **SiN1** and **SiN2**; the more redshifted absorption band corresponding to a HOMO \rightarrow LUMO transition. The HOMO of the silyloxyamines involves the π -system and the nitrogen lone pair. Interestingly, the LUMO is also delocalized on the silyl ether group. This evidences a partial charge transfer transition between the donor (the amine) and the acceptor (the O-Si-Si group). Silyloxyamines behave therefore as donor- π -acceptor molecules.

2/ Photolysis experiments:

It was reported ^[1,2] that silvloxy compounds can be cleaved upon photolysis at 254 nm to give the starting alcohols with yields ranging from 62-95%. The photolysis of **SiN1** and **SiN2** in degassed acetonitrile under UV irradiation (Hg-Xe lamp; 220 mW/cm²) was thus examined as shown in Figure 3. **SiN1** and **SiN2** do not generate the corresponding alcohols

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as the typical absorption bands of the parent hydroxy compounds at 462 and 526 nm are not observed. This behavior can suggest the occurrence of a Si-Si instead an O-Si bond cleavage. An increase of a broad absorption band between 350 nm and 400 nm for both silyloxyamines is also noted: it might correspond to the formation of a photolysis product resulting from the attack of a silyl radical to the aromatic ring i.e. the addition of R₃Si[•] onto aromatic rings is well documented.^[21]

3/ ESR Spin-Trapping experiments:

Under direct irradiation of SiN1 and SiN2, two radicals are generated and trapped by PBN (Figure 4). The hyperfine splitting constants for both the nitrogen (a_N) and the hydrogen (a_{H}) of these adducts are reported in Table 2. They are assigned (Scheme 3) to the known trimethylsilyl radical^[11] (a) and tentatively to the carbon centered radicals (b and c). No radicals are observed when irradiating the amino alcohols in the same conditions. These results clearly support the Si-Si cleavage; the O-Si bond cleavage can be probably ruled out as the (CH₃)₃Si-Si[•](Me)₂ radical is not observed here. Oxygen and carbon centered radicals can exhibit in some case similar spectral parameters $(a_N \text{ and } a_H)$;^[14a] however, the oxvoen centered radicals will correspond here to phenoxy derived radicals which are fairly stable. The addition of these radicals to PBN is probably not highly favorable. Moreover, in previous works, the parameters for phenoxy derived radicals were found quite different to carbon centered radicals.^[14b] Independently, phenoxy derived radicals can be easily characterized by Laser Flash Photolysis experiments (intense absorption and specific reactivity - see below the LFP data). This absorption is clearly not observed in our LFP experiments ruling out the O-Si cleavage in agreement with the Molecular Orbital calculations and ESR spin trapping results. The presence of **b** and **c** is accounted for by a hydrogen abstraction process. The generation of these radicals is in good agreement with the high polymerization initiating ability observed for SiN1 and SiN2 (see below) i.e. these latter radicals being good polymerization initiating structures.^[8b] In **SiN1**, an intramolecular process ($\Delta H = -7.1$ kcal/mol; from MO calculations) can be favorable as it involves the intermediate conformation of a sixmember ring. In SiN2, the c ($a_N = 14.4$; $a_H = 2.4G - Table 2$) amount increases with the irradiation time in line with a bimolecular process ($\Delta H = -2.4$ kcal/mol; MO calculations). The hyperfine splitting constants for the adduct of c are in excellent agreement with those observed recently for aminoalkyl radicals.^[14d]





4/ Energetic Considerations:

The triplet energy levels (E_T) of **SiN1** and **SiN2** are calculated as 75.1 and 66 kcal/mol, respectively (at UB3LYP/6-31G* level). The different bond dissociation energies (BDE) associated with the cleavage of the Si-Si and Si-O bonds in **SiN1** and **SiN2** are summarized in Scheme 4. The BDEs(Si-O) are weaker than previously reported data (BDE(Si-OR)~110 kcal/mol with R=alkyl).^[28] In the present work, these weaker BDEs(Si-O) can be ascribed to the formation of stabilized phenoxy radicals. For BDEs(Si-Si) a good agreement with literature data is found.^[28]

 Interestingly, the cleavage of the Si-Si bond is energetically more favorable than that of the Si-O bond by about 9 and 13 kcal/mol for **SiN1** and **SiN2**, respectively; the (Si-Si) BDEs are lower than the (Si-O) BDEs for both compounds; the Si-Si triplet cleavage is exothermic for **SiN1** and athermic for **SiN2**; the Si-O triplet cleavage is endothermic. A singlet state cleavage should be obviously feasible in both **SiN1** and **SiN2** for the Si-Si bonds. The Si-O fragmentation is not, however, experimentally supported. The triplet state of **SiN1** and **SiN2** is not found dissociative in MO calculations but this does not exclude the possibility of a cleavage process.



5/ Laser flash photolysis (LFP) investigation:

The transient absorption spectra recorded immediately after the laser flash excitation (at 266 nm) of SiN1 and SiN2 as well as the corresponding starting amino alcohols (Figure 5) are similar. The 8-hydroxyjulolidine and SiN1 absorption maximum wavelength is located at 470 nm whereas it shifts to a slightly higher wavelength (about 490 nm) for diethylaminophenol and SiN2. The transients decay in the 5-10 µs range. They are ascribed to the radical cation centered on the N-atom and probably generated through a photoionization process. Indeed, this is consistent with the reported formation of a radical cation upon laser excitation of various aliphatic and aromatic amines in a freon glass,^[17,18] for triethylamine, 1azabicyclo[3.3.3]undecane, 1-azabicyclo[2.2.2]octane or 1,4-diazabicyclo[2.2.2]octane) in acetonitrile solutions.^[19-20] Moreover, TD-DFT calculations on the possible radical cation (at the B3LYP/6-311G** level; after full geometry optimization) show here that the observed transient spectra for 8-hydroxyjulolidine and SiN1, 3-diethylaminophenol and SiN2 guite satisfactorily correlate with the calculated spectra (vertical bars in Figure 5). Radicals a, b and **c** are not observed due to their lack of significant absorption.^[11,12,21] The phenoxy radicals usually characterized ^[24] by an intense absorption at about 400 nm are not observed here in full agreement with ESR-ST results which have ruled out a O-Si cleavage for the investigated compounds.

The formation of the radical cation can be assumed as a competitive pathway to the Si-Si cleavage process since the absorption corresponding to this species is very similar for both **SiN1**/8-hydroxyjulolidine and **SiN2**/diethylamino-phenol evidencing a weak influence of the silyl moiety on this transient.

The Si-Si cleavage can result from the significant electron density transfer from the donor (julolidine for example) to the acceptor (silyl ether group) observed in the LUMOs. A similar behavior has been pointed out ^[22] in a donor-acceptor molecule (3,5-dimethyl-4-(9-anthracenyl)julolidine) where an intramolecular charge transfer occurs from julolidine to anthracene.

When exciting benzophenone (BP) in the presence of **SiN2**, the BP ketyl radical is detected (ketyl radical quantum yield = 0.8; the procedure to measure this parameter is presented in detail in [8c]). The BP/**SiN2** interaction rate constant is measured as $3.1 \times 10^9 \text{ M}^{-1} \text{ s}^{-1}$. The oxidation potentials of EDB and **SiN2** are 1.08 V and 0.77 V, respectively. Using a reduction potential of -1.79 eV and a triplet state energy of 2.98 eV for BP, exothermic electron-transfer reactions ($\Delta G = -0.11 \text{ eV}$ and -0.42 eV for BP/EDB and BP/**SiN2**, respectively) are calculated from the Rehm-Weller equation (Eq 1). These results are in favor of an usual electron transfer followed by a proton transfer observed for amines.^[11] An aminoalkyl radical is concomitantly generated.

6/ Free Radical photopolymerization ability:

Interestingly, the **SiN1** and **SiN2** compounds proposed as Type I photoinitiators are liquids: this improves their solubility in monomers compared to the starting alcohol powders. The photopolymerization profiles of TMPTA in laminated (to avoid oxygen regeneration) and aerated conditions under a polychromatic irradiation (Xe-Hg lamp) are shown in Figure 6. The polymerization rates R_p and the final conversions after 400 s of irradiation are given in Table 3. In laminate, **SiN1** and **SiN2** are better PIs than 8-hydroxyjuloidine where the initiating radicals are presumably formed through unclear by-side interactions of this amino alcohol with the monomer. Due to their quite low absorption (Figure 1) for the principal emission bands of Hg-Xe lamp i.e. $\lambda > 300$ nm, their efficiency is likely lower than that encountered with other Type I PIs. **SiN2** is better than **SiN1** in agreement with the above mentioned energetic considerations for a more efficient Si-Si cleavage process. Under air, as expected in such a low viscosity matrix,^[25] the polymerization rate dramatically drops down. However, interestingly, **SiN1** compared to 8-hydroxyjuloidine leads to a significant polymerization process under air. This behavior is highly worthwhile since many classical PIs do not allow initiation for these severe conditions. This evidences the formation of silyl

radicals i.e. it is well known that these species are useful for polymerization in aerated conditions (to overcome the oxygen inhibition).^[25]

Under visible light (Xe lamp; $\lambda > 400$ nm), in an aerated matrix, both the rate of polymerization and final conversion decrease (see Figure 7 for **SiN1**). To speed up the polymerization, experiments were done using **SiN1** in the presence of tris(trimethylsilyl)silane (TTMSS; 1 wt%) already shown as an excellent additive for photopolymerization under air.^[7,23,25] A remarkable enhancement is noted as quite good photopolymerization profiles and high conversion (~ 60%) were obtained (Figure 7). The better photoinitiating ability of **SiN1** in the presence of TTMSS is full agreement with previous data on other photoinitiators. The ability of TTMSS to overcome the oxygen inhibition in FRP process is already described in [25].

Based on the LFP experiments, silyloxyamines should also work as Type II PIs. This is exemplified (Figure 8) by the benzophenone (BP)/**SiN2** system in laminated conditions using a polychromatic light exposure (Xe-Hg lamp). Compared to the BP/EDB reference system, a remarkable increase of the polymerization rate (R_p) is noted (Table 4). The direct light absorption by **SiN2** leading to a silyl radical can contribute to the R_p enhancement.

Conclusion:

In the present paper, the photolysis of two new silyloxyamines derived from pentamethyldisilane is investigated. Compared to usual super silyl ethers, they cannot be deprotected upon photolysis as they do not yield the starting alcohol (the Si-Si bond is weaker than the Si-O bond). On the opposite, the generation of the silyl radicals allows to use of these compounds as photoinitiators. Some modifications of the chromophoric group (for example by introducing more delocalized π systems) should allow tuning of the absorption towards the visible due to the charge transfer character of the HOMO-LUMO transition, enhance the light absorption properties and, hence, the polymerization ability of these compounds: this new concept opens up a new way for the design of efficient visible-near UV absorbing PIs in the Radiation Curing area.^[26] This concept might also be used in non linear optics or two-photon absorption applications.^[27]

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Tables:

Table 1. Absorption maxima of 8-hydroxyjulolidine, 3-diethylaminophenol, SiN1 and SiN2 in acetonitrile.

	SiN1	8-	SiN2	3- diathylaminanhanal
		nyaroxyjulollalne		dietnylaminoprienol
Absorption	267, 303	267, 303, 462	262, 301	262, 301, 526
maximum (nm)				

 indication

 indication

Table 2. Hyperfine coupling constants for the radical adducts of **SiN1** and **SiN2** measured by ESR Spin-Trapping (PBN).

		a _N (G)	a _H (G)
SiN1	а	14.8	6.3
	b	14.4	2.5
SiN2	а	14.8	6.3
	С	14.4	2.4

Table 3. Radical photopolymerization of TMPTA in the presence of different photoinitiating systems: polymerization rate $(R_p/[M_0] (s^{-1}))$ and final conversion after 400 s of irradiation.

	In lam	ninate	Under air	
Photoinitiators	Final conversion	R _p / [M ₀] x 100	Final conversion	R _p / [M ₀] x 100
	(%)	•	(%)	•
8-	62	1.4	-	-
hydroxyjulolidine				
SiN1	72	4.1	17	0.2
SiN2	68	2.2	-	-

(-) no photopolymerization

Table 4. Radical photopolymerization of TMPTA in the presence of BP/**SiN2** and BP/EDB: polymerization rate $R_p/[M_0]$ (s⁻¹) and final conversion after 400 s of irradiation.

	In laminate		
Photoinitiating	Final conversion	R _p / [M ₀] x 100	
systems	(%)	• -	
BP / EDB	71	16.7	
BP / SiN2	80	23.3	

Captions of Figures:

Figure 1. UV absorption properties: (A) 8-hydroxyjulolidine (dash line) and **SiN1** (solid line); insert: zoom between 300 and 600 nm. (B) 3-diethylaminophenol (dash line) and **SiN2** (solid line). In acetonitrile.

Figure 2. HOMO and LUMO of SiN1 (left) and SiN2 (right). From DFT calculations.

Figure 3 . Photolysis of (A) SiN1 and (B) SiN2 in acetonitrile (Hg-Xe lamp irradiation).

Figure 4. ESR spin-trapping spectra using PBN. 1) **SiN1** and 2) **SiN2**. UV-light irradiation at $\lambda > 310$ nm: A) experimental and B) simulated spectra.

Figure 5. Transient absorption spectra of A) 8-hydroxyjulolidine and **SiN1** and B) 3diethylamino-phenol and **SiN2** in acetonitrile ($\lambda_{exc} = 266$ nm). The oscillator strengths for the calculated UV-visible absorption spectra of the corresponding cations are given (sticks: see text).

Figure 6. Photopolymerization profiles of TMPTA in the presence of A) **SiN1** (1), 8hydroxyjulolidine (2) and **SiN2** (3) in laminated conditions (1% w/w) and B) **SiN1** (1), 8hydroxyjulolidine (2) in aerated conditions (1% w/w). Xe-Hg lamp; Lamp intensity = 44 mW/cm^2 .

Figure 7. Photopolymerization profiles of TMPTA in the presence of 1) 8-hydroxyjulolidine, 2) **SiN1,** 3) 8-hydroxyjulolidine/TTMSS (1 wt%) and 4) **SiN1**/TTMSS (1 wt%). Under air. Xe lamp; $\lambda > 400$ nm. Intensity = 60 mW / cm².

Figure 8. Photopolymerization profiles of TMPTA in the presence of 1) BP (1wt%)/EDB (3 wt%) and 2) BP (1 wt%)/**SiN2** (3 wt%). In laminate. Hg-Xe lamp; polychromatic light; intensity = 44 mW/cm².











Figure 4.



Figure 5.











Figure 7.









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